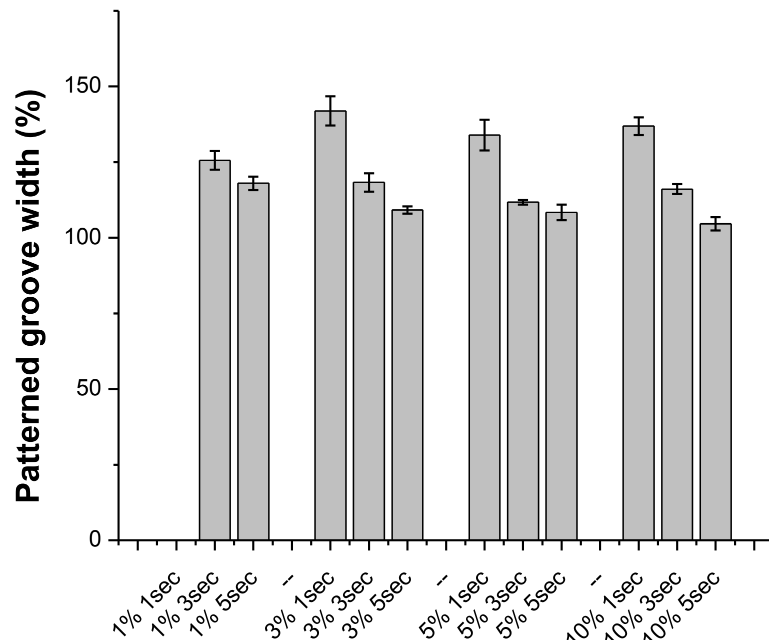

Figure S1. Patterned groove width with different UV exposure time and photoinitiator with 1, 3, 5, 10% concentration. Higher initial photoinitiator concentration requires shorter exposure time for patterning. The first condition (PI concentration: 1%, exposure time: 1 sec) was not measurable due to the under-crosslinked structure. Photomask width = 320 μm, spacer thickness = 150 μm (one coverslip) with constant UV intensity (7.5 mW/cm^2).